

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Koichi WATANABE et al.
Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si
OXIDE FILM THEREWITH
Appl. No.: 10/573,406
International Filing Date: 9/22/2004
371(c) Date: 3/27/2006
Examiner: Jason Berman
Art Unit: 1724
Confirmation Number: 2973

LETTER REGARDING SUPPLEMENTAL NOTICE OF ALLOWABILITY

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

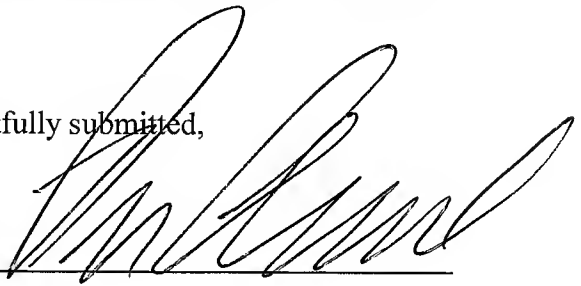
Sir:

Applicants note that claim 13 is not shown correctly in the Supplemental Notice of Allowability and should read as:

13. The process for producing an Si oxide film according to claim 12, wherein the Si oxide film is an optical thin film.

Respectfully submitted,

Date June 27, 2011

By 

FOLEY & LARDNER LLP
Customer Number: 22428
Telephone: (202) 945-6162
Facsimile: (202) 672-5399

Pavan K. Agarwal
Attorney for Applicant
Registration No. 40,888